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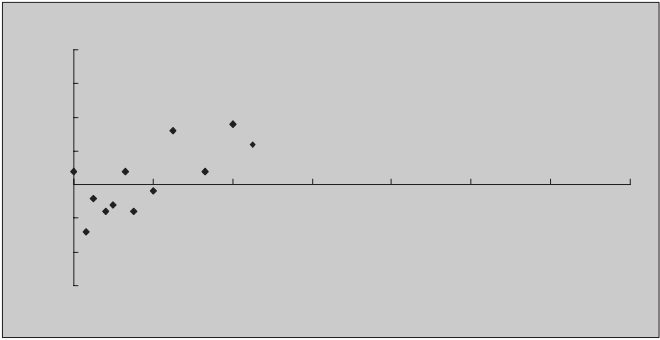
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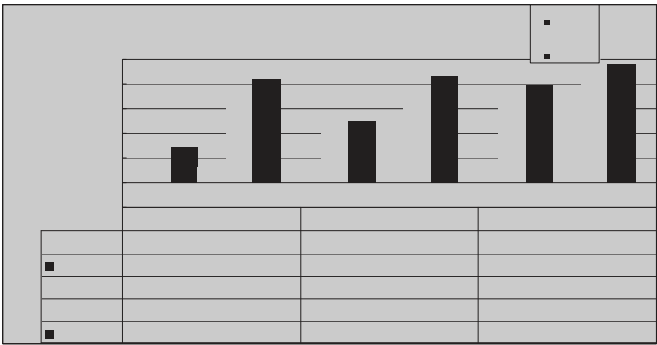
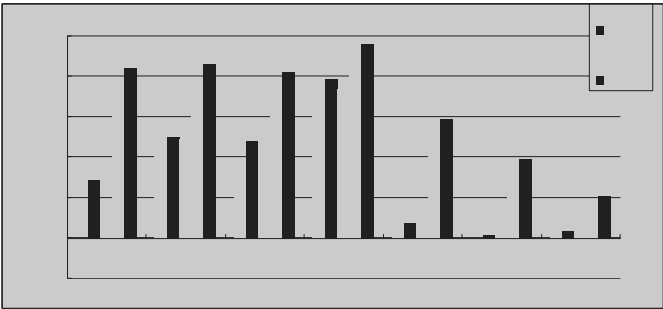
Particle removal, Functional water, SAPS megasonic technology

H_2O_2 in traditional SC1 solution.

In this paper, the method of sp

I





III

